

JSPP Program

April 21(Mon)

9:15–9:20	1. Opening Remarks and Opening Lecture (Chair: S. Hamaguchi)		
	Kunihide Tachibana	Japan	Review of my 40–years Research Work in Plasma Electronics
10:00–10:50	2. Simulations and diagnostics I (Chair:)		
10:00–10:25	Jae Koo Lee	Korea	Particle and Fluid Simulations of High–Pressure Micro Plasmas
10:25–10:50	Kanya Kusano	Japan	Study of Multi–scale and Multi–physics Dynamics with Macro–Micro Interlocked Simulations
10:50–11:10	— BREAK —		
11:10–12:05	3. Simulatrions and diagnostics II (Chair:)		
11:10–11:35	Akihiro Kono	Japan	Laser Thomson Scattering Diagnostics of Low–Temperature Plasmas : a Surface Wave Plasma Study and a Laser Disturbance Study
11:35–11:50	Hiroshi Akatsuka	Japan	Population Kinetics and Number Densities of Excited Species in Low–Pressure Discharge Nitrogen Plasma
11:50–12:05	Tomihito Ohba	Japan	Spatial Density Distribution of Argon Metastables in a 2f–CCP using Laser Absorption Spectroscopy
12:05–13:30	— LUNCH —		
13:30–15:15	4. Atmospheric pressure plasmas I (Chair:)		
13:30–14:00	Zoran Lj. Petrović	Serbia	Voltampere Characteristics of Low Current Micro Discharges and Transport Coefficients in CF _x /CF ₄ Mixtures
14:00–14:25	Christophe Leys	Belgium	Discharges in Bubbles and in Systems with Liquid Electrodes
14:25–14:50	Takehiko Sato	Japan	Characteristics of Low Temperature Plasma Flow at Atmospheric Pressure and its Application to Medical Field
14:50–15:15	Mirko Cernak	Slovakia	High–Speed, Low–Cost Atmospheric–Pressure Plasma Processing using Diffuse Coplanar Surface Barrier Discharge
15:15–15:45	— BREAK —		
15:45–17:15	5 Atmospheric pressure plasmas II (Chair:)		
15:45–16:10	Jan D. Skalny	Slovakia	Analysis of Ions Produced by DC Corona Discharges in Air at Atmospheric Pressure
16:10–16:35	Gordana Malović	Serbia	Mass Analysis of Products of Amospheric Pressure Discharges
16:35–17:00	Katsuhisa Kitano	Japan	LF Micro Plasma Jets with a Single HV Electrode and the Generation of Free Radicals in Liquids
17:00–17:15	Sergey Shapoval	Russia	Reflection Efficiency of Two–Dimensional Square Symmetry Unmagnetized Plasma Photonic Crystals in Microwave Wavelength Range
19:00–21:00	— BANQUET —		

April 22(Tue)

9:00–10:20	6. Semiconductor processing I (Chair:)		
9:00–9:25	Vahid Vahedi	USA	Plasma–Wall Interactions in Inductively Plasma Reactors and a Novel Method for Wall Condition Control
9:25–9:50	Song Yun Kang	Japan	Theoretical Study for Fluorocarbon Plasma Chemistry
9:50–10:05	Takashi Yagisawa	Japan	Modeling of a Feature Profile Evolution under Micro–Loading Effects in SiO ₂ Etching
10:05–10:20	Jozef Brcka	USA	The Effect of the Hydrogen in the RLSA CVD of the SiN _y (H ₂) Films
10:20–10:40	— BREAK —		
10:40–12:00	7. Semiconductor processing II (Chair:)		
10:40–11:05	Gottlieb S. Oehrlein	USA	Studies of Plasma–Polymer Interactions for Nanoscale Patterning of Materials
11:05–11:30	Kohei M. Itoh	Japan	Process Monitoring using Silicon Isotope Superlattices
11:30–11:45	James J. Munro	UK	Theoretical Study of a CF ₄ Plasma Chemistry using an Improved Set of Cross–Section Data
11:45–12:00	Fukutaro Hamaoka	Japan	Numerical Prediction of a Micro–Scale Etching of Si under Plasma Molding in 2f–CCP in SF ₆ /O ₂

12:00–13:30	— LUNCH —		
13:30–15:00	8. Poster Session (Chair:)		
15:00–15:10	— BREAK —		
15:10–16:40	9. New trends in plasma science (Chair:)		
15:10–15:35	Sadruddin Benkadda	France	Simulation Studies of the Nonlinear Dynamics of Drift Wave Turbulence in Dusty Plasma
15:35–16:00	Rikizo Hatakeyama	Japan	Plasma Processing Creation of Novel-Functional Nanocarbons
16:00–16:25	Masaharu Shiratani	Japan	Plasma Processes for Constructing Nanosystems in the 3rd Generation Nanotechnology
16:25–16:40	Galina V. Shpatakovskaya	Russia	Quasi-Classical Estimation of Ionization Potentials and Partition Functions of Ions
16:40–17:00	— BREAK —		
17:00–17:50	10. Atmospheric pressure plasmas III (Chair:)		
17:00–17:25	Eva Stoffels-Adamowicz	The Netherlands	Cold Plasma Treatment: Wound Care and Other Applications
17:25–17:50	Takanori Ichiki	Japan	Development of Atmospheric-Pressure MicroICP Jet and Its Application in Microsystem Technology
19:00–21:00	— BANQUET —		

April 23(Wed)

9:00–10:15	11. Atomic processes in plasmas I (Chair:)		
9:00–9:25	Mark D. Bowden	UK	Pulsed RF Plasmas: Controlling Plasma Properties by Pulse-Shaping
9:25–9:50	Hiroataka Toyoda	Japan	Measurement and Control of Energetic Rare Gas Atoms in Magnetron Plasma
9:50–10:15	Uwe Czarnetzki	Germany	Electric Field Reversals in the Sheath Region of Capacitively Coupled Radio Frequency Discharges at Different Pressures
10:15–10:35	— BREAK —		
10:35–11:50	12. Atomic processes in plasmas II (Chair:)		
10:35–11:00	Steve J. Buckman	Australia	Electron Scattering from CF ₂ Radicals
11:00–11:25	Takako Kato	Japan	Plasma Diagnostics using Spectroscopy and Atomic Database
11:25–11:50	Nigel J. Mason	UK	Data Required for Understanding Atmospheric Pressure Plasmas
11:50–12:20	13. General Discussion (Chair: S. Hamaguchi and S. Samukawa)		
12:20–12:30	Closing Remarks		
	Zoran Lj. Petrović	Serbia	